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APPLICATION NO.	Fil	ING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
09/843,563	04/26/2001		Mark A. Lucak	00AB179	9460
7	590	04/24/2003			
John J Horn			EXAMINER		
Rockwell Tech 1201 S. Second	Street, 8	8-T29	COLEMAN, WILLIAM D		
Milwaukee, WI 53204				ART UNIT	PAPER NUMBER

DATE MAILED: 04/24/2003

Please find below and/or attached an Office communication concerning this application or proceeding.

		Application No.	plication No. Applicant(s)				
ť	. Office Anti-us Communication	09/843,563	LUCAK ET AL.				
	Office Action Summary	Examiner	Art Unit				
		W. David Coleman	2823				
The MAILING DATE of this communication appears on the cover sheet with the correspondence address Period for Reply							
THE N - Exten after: - If the - If NO - Failur - Any re	ORTENED STATUTORY PERIOD FOR REMAILING DATE OF THIS COMMUNICATION IS COMMUNICATION IN COMMU	DN. R 1.136(a). In no event, however, may a re t. a reply within the statutory minimum of thirty riod will apply and will expire SIX (6) MONT tatute, cause the application to become ABA	ply be timely filed  (30) days will be considered timely.  HS from the mailing date of this communication.  NDONED (35 U.S.C. 6.133)				
1)🖂	Responsive to communication(s) filed on	23 October 2002 .					
2a)		This action is non-final.					
3)	☐ Since this application is in condition for allowance except for formal matters, prosecution as to the merits is						
closed in accordance with the practice under <i>Ex parte Quayle</i> , 1935 C.D. 11, 453 O.G. 213. <b>Disposition of Claims</b>							
4)⊠ Claim(s) <u>1-46</u> is/are pending in the application.							
4a) Of the above claim(s) <u>10-39</u> is/are withdrawn from consideration.							
5) Claim(s) is/are allowed.							
6)⊠ Claim(s) <u>1-9 and 40</u> is/are rejected.							
7)⊠ Claim(s) <u>41-47</u> is/are objected to.							
8) Claim(s) are subject to restriction and/or election requirement.							
Application Papers							
9) The specification is objected to by the Examiner.							
10) The drawing(s) filed on is/are: a) □ accepted or b) □ objected to by the Examiner.							
Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).							
11)☐ The proposed drawing correction filed on is: a)☐ approved b)☐ disapproved by the Examiner.							
If approved, corrected drawings are required in reply to this Office action.							
12)☐ The oath or declaration is objected to by the Examiner.							
Priority u	nder 35 U.S.C. §§ 119 and 120						
13) Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).							
a) ☐ All b) ☐ Some * c) ☐ None of:							
1. Certified copies of the priority documents have been received.							
2. Certified copies of the priority documents have been received in Application No							
<ul> <li>3. Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)).</li> <li>* See the attached detailed Office action for a list of the certified copies not received.</li> </ul>							
14) ☐ Acknowledgment is made of a claim for domestic priority under 35 U.S.C. § 119(e) (to a provisional application).							
a) ☐ The translation of the foreign language provisional application has been received.							
15) Acknowledgment is made of a claim for domestic priority under 35 U.S.C. §§ 120 and/or 121.							
Attachment(	•	_					
2) Notice	of References Cited (PTO-892) of Draftsperson's Patent Drawing Review (PTO-948) ation Disclosure Statement(s) (PTO-1449) Paper No(	5) Notice of Inf	ormal Patent Application (PTO-152)				

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#### **DETAILED ACTION**

#### Election/Restrictions

1. Applicant's election without traverse of group I invention, claims 1-9 in Paper No. 5 is acknowledged.

### Claim Rejections - 35 USC § 102

2. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

- (b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.
- 3. Claims 1-9 and 40 are rejected under 35 U.S.C. 102(b) as being anticipated by Albrecht et al., U.S. Patent 5,399,232.
- 4. Pertaining to claim 1, <u>Albrecht</u> discloses a semiconductor process as claimed. See FIGS.
  1-26 where Albrecht teaches a method of fabricating a MEMS structure, comprising the steps of
  (a) forming a recess 18 in an upper surface of a substrate;
- (b) attaching an etchable wafer 30 to the upper surface of the substrate, including a wafer portion from which a movable structure will be formed, the wafer portion being positioned over the recessed; and
- (c) etching downward in the wafer around the periphery of the movable portion to break through in to the recess, thereby releasing at least part of the movable structure from the substrate without the need for substantial undercutting (see FIGS. 10, 11 and 12).

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- 5. Pertaining to claim 2, <u>Albrecht</u> teaches the method as recited in claim 1, further comprising depositing a conductive layer 32 onto the wafer.
- 6. Pertaining to claim 3, <u>Albrecht</u> teaches the method as recited in claim 2, further comprising depositing a protective layer 56 (as seen I FIG. 18)onto an upper surface of the conductive layer 54.

Pertaining to claim 4, <u>Albrecht</u> teaches the method as recited in claim 2, wherein the conductive layer is selected from the group consisting of aluminum, copper, silver, gold and nickel.

- 7. Pertaining to claim 5, <u>Albrecht</u> teaches the method as recited in claim 3, wherein the protective laver is selected from the group consisting of silicon dioxide and silicon nitride.
- 8. Pertaining to claim 6, <u>Albrecht</u> teaches the method as recited in claim 1, wherein the wafer is selected from the group consisting of silicon, silicon carbide and gallium arsenide.
- 9. Pertaining to claim 7, <u>Albrecht</u> teaches the method as recited in claim 1, wherein the substrate is a non conductive substrate selected from the group consisting of glass, high resistivity

silicon, crystalline sapphire, and ceramic.

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10. Pertaining to claim 8, <u>Albrecht</u> teaches the method as recited in claim 1, wherein the substrate is a conductive substrate selected from the group consisting of silicon, silicon carbide, and gallium arsenide.

- 11. Pertaining to claim 9, <u>Albrecht</u> teaches the method as recited in claim 1, wherein the recess has beveled edges.
- 12. Pertaining to claim 40, Albrecht teaches the method as recited in claim 1, wherein step(c) further comprises forming a first stationary conductive element extending outwardly from the substrate (see FIG. 14).

## **Objections**

13. Claims 41-47 are objected to as being dependent upon a rejected base claim, but would be allowable if rewritten in independent form including all of the limitations of the base claim and any intervening claims.

# Conclusion

14. Any inquiry concerning this communication or earlier communications from the examiner should be directed to W. David Coleman whose telephone number is 703-305-0004. The examiner can normally be reached on 9:00 AM-5:00 PM.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Olik Chaudhuri can be reached on 703-306-2794. The fax phone numbers for the

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organization where this application or proceeding is assigned are 703-308-7722 for regular communications and 703-308-7721 for After Final communications.

Any inquiry of a general nature or relating to the status of this application or proceeding should be directed to the receptionist whose telephone number is 703-308-0956.

W. David Coleman Primary Examiner Art Unit 2823

WDC April 12, 2003